

Title (en)
LOW DENSITY POLISHING PAD

Title (de)
POLIERKISSEN MIT NIEDRIGER DICHT

Title (fr)
TAMPON DE POLISSAGE À FAIBLE DENSITÉ

Publication
EP 3027363 A1 20160608 (EN)

Application
EP 14747270 A 20140717

Priority
• US 201313955398 A 20130731
• US 2014047065 W 20140717

Abstract (en)
[origin: US2015038066A1] Low density polishing pads and methods of fabricating low density polishing pads are described. In an example, a polishing pad for polishing a substrate includes a polishing body having a density of less than 0.5 g/cc and composed of a thermoset polyurethane material. A plurality of closed cell pores is dispersed in the thermoset polyurethane material.

IPC 8 full level
B24B 37/24 (2012.01)

CPC (source: EP US)
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Citation (search report)
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US 2015038066 A1 20150205; CN 105408063 A 20160316; CN 105408063 B 20180130; EP 3027363 A1 20160608; EP 3027363 B1 20200115; JP 2016525459 A 20160825; JP 2017042910 A 20170302; JP 2019077036 A 20190523; JP 6415521 B2 20181031; JP 6517802 B2 20190522; KR 101801693 B1 20171127; KR 20160027075 A 20160309; SG 11201600242P A 20160226; TW 201509595 A 20150316; TW I579106 B 20170421; WO 2015017138 A1 20150205

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US 201313955398 A 20130731; CN 201480042621 A 20140717; EP 14747270 A 20140717; JP 2016234679 A 20161202; JP 2016531739 A 20140717; JP 2018238139 A 20181220; KR 20167002464 A 20140717; SG 11201600242P A 20140717; TW 103126073 A 20140730; US 2014047065 W 20140717